



# National Institute of Standards & Technology

## Certificate of Analysis

### Standard Reference Material 3150

#### Spectrometric Standard Solution

#### Silicon

Batch Code 490404

This Standard Reference Material (SRM) is intended for use in atomic absorption spectrometry, optical emission (plasma) spectrometry, spectrophotometry, or any other analytical technique that requires aqueous standard solutions for calibrating instruments. SRM 3150 is a single element solution prepared gravimetrically to contain 10 mg/mL of silicon in water. The certified value is based on a gravimetric assay of the prepared solution. The value has been adjusted upward by 0.1% relative, based on estimated transpiration losses of solvent through the container walls of 0.2% relative per year. The density of the solution at 22 °C is 1.042 g/mL.

Metal	Concentration (mg/mL)	Source Purity, %	Acid Conc. (V/V) Approximate
Si	9.97 ± 0.03	Na <sub>2</sub> SiO <sub>3</sub> · 9H <sub>2</sub> O(99.99%)	Water

The uncertainty in the certified value is calculated as

$$U = (2u_c + 0.001V) \text{ mg/mL}$$

where  $u_c$  is the "combined uncertainty" calculated according to the ISO Guide [1,2]. The value  $u_c$  is intended to represent, at the level of one standard deviation, the combined effect of uncertainty components associated with volumetric, gravimetric, and instrumental factors relevant to the gravimetric assay of the prepared solution. The additional quantity,  $0.001V$ , is an allowance for transpiration of the solution through the container walls, which is estimated to be ± 0.1% of the certified value during the one-year period of validity of the certification.

The combined uncertainty consists of Type B components due to uncertainty in the balance reading and uncertainty in the material handling and dilution. Each component is derived from its corresponding uniform probability distribution by division by  $\sqrt{3}$ .

SRM 3150 was prepared by T.A. Butler of the NIST Inorganic Analytical Research Division; gravimetric and emission spectrometric analyses were made by T.A. Butler, J.A. Norris, and T.W. Vetter.

The technical and support aspects involved in the preparation, certification, and issuance of this SRM were coordinated through the Standard Reference Materials Program by J.S. Kane.

Gaithersburg, MD 20899  
July 6, 1994

Thomas E. Gills, Chief  
Standard Reference Materials Program

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## Procedures for Use

**Stability:** This certification is valid for one year from the shipping date, provided the SRM solution is kept tightly capped and stored under normal laboratory conditions. NIST will monitor the stability of representative solutions from this SRM lot, and if any changes occur that invalidate this certification, NIST will notify purchasers.

**Preparation of Working Standard Solutions:** All solutions should be brought to  $22 \pm 1$  °C and all glass or plastic surfaces coming into contact with the standard must have been previously cleaned. A working standard solution can be prepared from the SRM solution by serial dilution. Dilutions should be made with certified volumetric class A flasks and 5 or 10 mL class A pipets. All volumetric transfers of solutions should be performed using a proven analytical technique. Each dilution should be acidified with an appropriate high-purity acid and diluted to calibrated volume using high-purity water. The stability of the working standard solution will depend on the final acid concentration; therefore, care should be exercised to ensure that the final acid concentration of the dilution closely approximates that of the SRM. To achieve the highest accuracy, the analyst should prepare daily working solutions from 100 µg/mL dilutions of the original SRM solution.

## REFERENCES

- [1] *"Guide to the Expression of Uncertainty in Measurement"*, ISBN 92-67-10188-9, 1<sup>st</sup> Ed. ISO, Switzerland, 1993.
- [2] Taylor, B.N. and Kuyatt, C.E., "Guidelines for Evaluating and Expressing the Uncertainty of NIST Measurement Results" NIST Technical Note 1297, National Institute of Standards and Technology, Technology Administration, U.S. Department of Commerce, 1993.